# The effect of IIIB and IVB elements on the superconducting properties of zirconium-based amorphous alloys

# A. INOUE<sup>\*</sup>, Y. TAKAHASHI<sup>‡</sup>, T. MASUMOTO

The Research Institute for Iron, Steel and Other Metals, <sup>‡</sup> Graduate School, Tohoku University, Sendai 980, Japan

Zr-based amorphous alloys exhibiting superconductivity have been found in ternary  $Zr_{85}Si_{15-x}M_x$  and  $Zr_{85}Ge_{15-x}M_x$  (M = B, AI, C, Si, Ge or Sn) systems by a melt-spinning technique. Specimens are in the form of continuous ribbons of 1 mm wide and 0.02 mm thick. The M content in the amorphous alloys is limited to less than 10 at % B, 7 at % Al, 3 at % C, 9 at % Sn for the Zr–Si–M system and less than 7 at % B, 7 at % Al, 3 at % C and 9 at % Sn for the Zr-Ge-M system. The hardness and crystallization temperature increase significantly with the substitution of B, C or Al for Si or Ge, but the effect of the other elements is less significant. The superconducting transition temperature,  $T_{\rm c}$ , rises with the substitution of C, AI, Sn or B for Si, whereas the substitution by Ge causes a slight lowering of  $T_c$ . The effectiveness of element M on the rise of  $T_c$  decreases in the order C > AI > Sn > B > Si > Ge. The upper critical field gradient at  $T_c$ ,  $(dH_{c2}/dT)_{T_c}$ , and the electrical resistivity at 4.2 K,  $\rho_n$ , decrease from 2.30  $\times$  10<sup>6</sup> to 1.97  $\times$  10<sup>6</sup> Å m<sup>-1</sup> K<sup>-1</sup> and from 2.70 to 2.00  $\mu\Omega m$ , respectively, with the amount of element M. The coefficient of low-temperature electronic specific heat,  $\gamma$ , and the dressed density of electronic states at the Fermi level,  $N^*(E_f)$ , were calculated from the experimentally measured values of  $\rho_n$  and  $(dH_{c2}/dT)_{T_c}$  using the strong-coupling theories. From the comparison of  $T_c$  with their calculated parameters, it was found that the rise of  $T_c$  with the substitution of Si by B, C, AI or Sn is caused by the increase in  $\gamma$  and  $N^*(E_f)$ . The GL parameter,  $\kappa$ , estimated by using the GLAG theory, decreases from 100 to 78 by the substitution of elements M for Si and it is inferred that the decrease in the dirtiness is also attributable to the rise of  $T_{c}$ .

# 1. Introduction

Among the amorphous superconductors found to date, the alloy composition of the superconductors tors exhibiting relatively high superconducting transition temperatures  $(T_c)$  is limited to the metal-metalloid type [1.2]. It has been demonstrated for La [3-5], Nb [6, 7], Mo [8-11] and Ti-Nb [12, 13] based amorphous alloys that the superconducting properties are sensitively affected by both the metal and metalloid components. However, the effect of metalloid elements on  $T_c$ 

is significantly different among their alloy system, e.g., the lowering of  $T_c$  by 1 at % addition becomes large in the order of Ge > Si > As > B > P for the Nb-, Mo- and Ti-Nb-base alloys, but that for the La-based alloys is in the order of Si > Ga > Ge. Thus, there is no systematic information about the change in  $T_c$  with metalloid composition.

Recently, it has been reported [14, 15] that melt-quenched Zr-(Si or Ge) binary alloys form an amorphous phase in wide composition ranges and exhibit a superconducting transition whose

\*Present address: Bell Laboratories, 600 Mountain Avenue, Murray Hill, New Jersey 07974, USA. <sup>‡</sup>Present address: Sonny Magnet Products Ltd, Tagajo 985, Japan.

Zr <sub>85</sub> Si <sub>15-x</sub> M <sub>x</sub>	Solute element concentration, x (at%)					
	<u>v</u> ş	i 12				
Boron	Amorphous	Crystalline				
Carbon	Am. Cry	stalline				
Aluminium	Amorphous	Crystalline				
Germanium	Amo	rphous				
Tin	Amorphous	Crystalline				

Figure 1 Composition range for the formation of an amorphous phase in the  $Zr_{ss}Si_{1s-x}M_x$  (M = B, C, Al, Ge or Sn) alloys.

temperature is in the range 2.05 to 3.20 K. These alloys appear to be favourable alloy systems for studying systematically the effect of metalloid elements on the superconducting properties and for comparing the present results with those [3-13] of the La-, Nb-, Mo- and Ti-Nb-base amorphous alloys. The purpose of this paper is to clarify the effect of group IIIB and IVB elements (M = C, Al, B, Si, Ge or Sn) on the superconducting properties and the related parameters of  $Zr_{85}Si_{15-x}M_x$  and  $Zr_{85}Ge_{15-x}M_x$  amorphous alloys prepared by the melt-quenching technique.

## 2. Experimental procedure

The alloy systems selected for the present work are  $\operatorname{Zr}_{85}\operatorname{Si}_{15-x}M_x$  and  $\operatorname{Zr}_{85}\operatorname{Ge}_{15-x}M_x$  (M = C, Al, B, Si, Ge or Sn). The crystalline alloys, from which the specimens used in this experiment were prepared, were made by melting each pure element of Zr, Si, Ge and M under an argon atmosphere in an arc furnace. To achieve homogeneity, the alloys were repeatedly turned over and remelted. The compositions of alloys reported are the nominal ones since the losses of Si and Ge during melting were negligible. Long ribbon specimens were produced by squirting a stream of molten melted with a levitation furnace under argon through a quartz nozzle on a single spinning roller which was rotating at a high speed of about 4000 rpm. The ribbons thus produced were about 1 mm wide by about 20  $\mu$ m thick. The methods of characterizing the as-quenched phases by X-ray and electron metallographic techniques are described elsewhere [6]. Crystallization temperature  $(T_x)$  was evaluated in a differential scanning calorimeter (DSC) at a heating rate of  $20 \,\mathrm{K\,min^{-1}}$ . Hardness  $(H_v)$  was measured by a Vickers microhardness tester with a 100 g load.

All measurements of superconducting properties,  $T_c$ ,  $J_c(H)$  and  $H_{c2}(T)$  were done resistively

7. 0. 14	Solute element concentration, x (at						
2r <sub>85</sub> Ge <sub>15-x</sub> M <sub>x</sub>	0 5	10 15					
Boron	Amorphous	Crystalline					
Carbon	Am Crystalline						
Aluminium	Amorphous	Crystalline					
Silicon	Amor	phous					
Tin	Amorphous	Crystalline					

Figure 2 Composition range for the formation of amorphous phase in the  $Zr_{ss}Ge_{1s-x}M_x$  (M = B, C, Al, Si or Sn) alloys.

using a conventional four-probe technique. The temperature was measured with an accuracy of  $\pm 0.01$  K using a calibrated germanium thermometer. The magnetic field up to  $7.16 \times 10^6$  A m<sup>-1</sup> was applied perpendicularly to the specimen surface and feed current.

## 3. Results

#### 3.1. Formation range of the amorphous phase

The formation of the amorphous phase by the melt-quenching technique was examined in the binary systems of Zr-B, Zr-Al, Zr-C, Zr-Si, Zr-Ge and Zr-Sn and it was demonstrated [14, 15] that the Zr-Si and Zr-Ge alloys showed an amorphous phase with good bend ductility, which is shown by the  $180^{\circ}$  bending, whereas no amorphous phase was found in the other alloy systems. The formation range of the binary amorphous alloys is in the range 12 to 24 at % Si and 12 to 20 at % Ge and these alloys appear to have the highest amorphous phase-forming tendency in the vicinity of 15 at % Si or Ge. Therefore, the metalloid content of the samples used in the present work was fixed at 15 at %.

The composition ranges in which the totally amorphous phase formed in the  $Zr_{85}Si_{15-x}M_x$ (M = B, C, Al, Ge or Sn) and  $Zr_{85}Ge_{15-x}M_x$ (M = B, C, Al, Si or Sn) ternary systems are shown in Figs. 1 and 2. It can be seen that the range is limited to less than 10 at % B, 7 at % Al, 3 at % C or 9 at % Sn for  $Zr_{85}Si_{15-x}M_x$  alloys and less than 7 at % B, 7 at % Al, 3 at % C or 9 at % Sn for  $Zr_{85}Ge_{15-x}M_x$  alloys, whereas in the  $Zr_{85}(Si-Ge)_{15}$ alloys an amorphous phase is formed over the whole composition region. Thus, the effect of elements M on the amorphous phase-forming tendency of the Zr-based alloys is greatest for Si followed for Ge, Sn, B, Al and then C, suggesting the tendency that the amorphous phase-forming



Figure 3 Change in Vickers hardness  $(H_v)$  for  $Zr_{ss}Si_{1s-x}M_x$ (M = B, C, Al, Ge or Sn) amorphous alloys with concentration of element M.

ability enhances by the addition of elements M having a large average outer electron concentration and a moderately large atomic size. This is consistent with the previous results that the formation of an amorphous phase is significantly influenced by atomic configuration [16] and chemical bonding nature [17] of constituent elements.

## 3.2. Hardness and crystallization temperature

Figs. 3 and 4 show the change in Vickers hardness  $(H_v)$  value of amorphous  $Zr_{85}Si_{15-x}M_x$  and  $Zr_{85}Ge_{15-x}M_x$  alloys as a function of M concentration. The change appears to be divided into the following three groups: (1) C, B and Al which enhance the  $H_v$  value, (2) Ge which causes a decrease in  $H_v$ , and (3) Sn which results in no significant change. On the other hand, the value of  $H_v$  of  $Zr_{85}Ge_{15-x}M_x$  alloys increases with the substitution of C, B, Al, Sn or Si for Ge. From the compositional dependence of  $H_v$  shown in Figs. 3 and 4, it is concluded that the effect of additional elements M on the increase in hardness decreases in the order C > B > Al > Sn > Si > Ge.

Additionally, the effect of the elements M on the crystallization temperature  $(T_x)$  of amorphous  $Zr_{85}Si_{15-x}M_x$  and  $Zr_{85}Ge_{15-x}M_x$  alloys was examined and the  $T_x$  values are plotted as a function of M concentration in Figs. 5 and 6. The effect of elements M is very similar in both the



Figure 4 Change in Vickers hardness  $(H_v)$  for  $\operatorname{Zr}_{85}\operatorname{Ge}_{15-x}M_x$ (M = B, C, Al, Si or Sn) amorphous alloys with concentration of element M.

alloy systems and decreases in the order C > B > Al > Sn > Si > Ge, in good agreement with the tendency for hardness.

#### 3.3. Superconducting properties

Fig. 7 shows the reduced electrical resistance curves in the vicinity of  $T_c$  in the case of no applied magnetic field for the amorphous  $Zr_{85}Si_{15-x}M_x$ (M = C, Al, Ge, or Sn) alloys. The transition occurs sharply with a temperature width ( $\Delta T_c$ ) of less than 0.2 K from the relatively high electrical resistivity values ranging from 2.00 to 2.70  $\mu\Omega$ m and there is no system change in  $\Delta T_c$ with the substitution of elements M for Si even



Figure 5 Change in the crystallization temperature  $(T_x)$  for  $Zr_{ss}Si_{1s-x}M_x$  (M = B, Al, Ge or Sn) amorphous alloys with concentration of element M.



Figure 6 Change in crystallization temperature  $(T_x)$  for  $Zr_{85}Ge_{15-x}M_x$  (M = B, C, Al, Si or Sn) amorphous alloys with concentration of element M.

though the  $T_{c}$  value rises significantly. Figs. 8 and 9 show the plots of  $T_c$  and  $\Delta T_c$  of the amorphous  $Zr_{85}Si_{15-x}M_x$  and  $Zr_{85}Ge_{15-x}M_x$  alloys as a function of M content. The  $T_c$  value is 2.65 K for Zr<sub>85</sub>Si<sub>15</sub>, rises with the replacement of Si by C, Al, Sn or B and reaches the highest value of 3.91 K for Zr<sub>85</sub>Si<sub>8</sub>Al<sub>7</sub>. Conversely, the substitution of Ge for Si results in a slight lowering of  $T_c$ . The similar compositional dependence is recognized in  $Zr_{85}Ge_{15-x}M_x$  alloys and the  $T_c$  value rises with the replacement of Ge by C, Al, Sn or Si and the highest value attained is 3.80 K for Zr<sub>85</sub>Ge<sub>8</sub>Al<sub>7</sub>. The above results indicate that the effect of elements M on the rise of  $T_{c}$  is similar between the  $Zr_{85}Si_{15-x}M_x$  and  $Zr_{85}Ge_{15-x}M_x$  alloys and the effectiveness decreases in the order Al > Sn > B >C > Si > Ge.



Figure 7 Change in the reduced electrical resistance as a function of temperature for  $Zr_{ss}Si_{1s}$  and  $Zr_{ss}Si_{1s-x}M_x$  (M = C, Al, Ge or Sn) amorphous alloys.



Figure 8 Change in the superconducting transition temperature  $(T_c)$  and the transition width  $(\Delta T_c)$  for  $\operatorname{Zr}_{85}\operatorname{Si}_{15-x}M_x$ (M = B, C, Al, Ge or Sn) amorphous alloys with concentration of element M.

The upper critical magnetic field,  $H_{c2}$ , was measured at various temperatures ranging from 1.5 K to  $T_{c}$ . Fig. 10 shows a plot of the  $H_{c2}$  value of amorphous  $Zr_{85}Si_{15-x}M_x$  (M = B, Al, C, Ge or Sn) alloys as a function of temperature. Here,  $H_{c2}$  was defined as being the applied magnetic field at which the resistance of the samples begins to deviate from its normal value. The solid lines in the figure represent a linear extrapolation at  $T_{\rm c}$ .  $H_{c2}$  increases linearly with decreasing temperature over almost the whole temperature range and the gradient at  $T_c$ ,  $(dH_{c2}/dT)_{T_c}$ , is  $2.06 \times 10^6 \text{ A m}^{-1}$  $K^{-1}$  for  $Zr_{85}Si_5B_{10}$ ,  $2.11 \times 10^6 \text{ A m}^{-1} \text{ K}^{-1}$  for  $Zr_{85}Si_{10}Al_5$ ,  $1.97 \times 10^6 \text{ A m}^{-1} \text{ K}^{-1}$  for  $Zr_{85}Si_{12}C_3$ ,  $2.29 \times 10^6$  A m<sup>-1</sup> K<sup>-1</sup> for Zr<sub>85</sub>Ge<sub>15</sub> and  $1.97 \times$  $10^6\;A\,m^{-1}\;K^{-1}$  for  $Zr_{85}Si_6Sn_9,$  indicating the tendency that the substitution of elements M for Si results in a decrease in the gradient.



Figure 9 Change in the superconducting transition temperature  $(T_c)$  and the transition width  $(\Delta T_c)$  for  $\operatorname{Zr}_{85}\operatorname{Ge}_{15-x}M_x$ (M = B, C, Al, Si or Sn) amorphous alloys with concentration of element M.



Figure 10 Change in the upper critical magnetic field  $H_{c2}$  as a function of temperature for  $Zr_{s5}Si_{15}$  and  $Zr_{s5}Si_{15-x}M_x$  (M = B, C, Al, Ge or Sn) amorphous alloys.

#### 4. Discussion

As shown in Figs. 8 and 9, the  $T_c$  of amorphous Zr<sub>85</sub>Si<sub>15</sub> alloy rises significantly with the substitution of B, Al, C or Sn for Si, whereas the subsitution of Ge for Si results in a slight lowering of  $T_{\rm c}$ . In this section, we shall investigate the origin of such a compositional dependence of  $T_{c}$  by evaluating some fundamental superconducting parameters. From the measured values of the upper critical field gradient at  $T_c$ ,  $(dH_{c2}/dT)_{T_c}$ , and residual electrical resistivity,  $\rho_n$ , at 4.2 K, we can estimate some fundamental parameters dominanting superconductivity such as the electronic dressed density of states  $N^*(E_f)$ , at the Fermi level, the coefficient of low-temperature electronic specific heat,  $\gamma$ , the Ginzburg-Landau (GL) coherence length  $\xi_{GL}(0)$ , the extrinsic GL parameter  $\kappa$ , the penetration depth,  $\lambda_0$ , and the electronic diffusivity, D, by using the Ginzburg-Landau-Abrikosov-Gorkov (GLAG) theory for "dirty" superconductors (e.g. [18]). The details of the expressions derived from the GLAG theory have been already presented elsewhere [19]. Values of  $\gamma$  and  $N^*(E_f)$  thus obtained are summarized in Table I, together with the values of  $T_{\rm c}$ ,  $\Delta T_{\rm c}$ ,  $\rho_{\rm n}$  and  $dH_{\rm c2}/dT$  at  $T_{\rm c}$ . The  $\gamma$  and  $N^*(E_{\rm f})$ values for  $Zr_{85}Si_{15}$  amorphous alloys are 239 J  $m^{-3} K^{-2}$  and  $1.91 \times 10^{47}$  states  $m^{-3} J^{-1} spin^{-1}$ , respectively, and tend to increase with the sub-



Figure 11 Relationship between  $T_c$  and  $\gamma$  for  $Zr_{85}Si_{15}$ and  $Zr_{85}Si_{15-x}M_x$  (M = B, C, Al, Ge or Sn) amorphous alloys.

stitution of B, Al, C, or Sn for Si. On the other hand, the substitution of Ge for Si results in the decreases of  $\gamma$  and  $N^*(E_f)$ . It is well known [20] that the  $T_{\rm c}$  value for a strong coupling superconductor is dominated by the Debye temperature,  $\theta_{\rm D}$ , the electron-phonon coupling constant,  $\lambda$ , and/or the bare density of states at the Fermi level,  $N(E_f)$ , and there is a close relation whereby the larger the values of  $\theta_{\mathbf{D}}$ ,  $\lambda$  and  $N(E_{\mathbf{f}})$  the higher is  $T_{c}$ . Considering the fact [18] that there exist the relations of  $N^*(E_f) = N(E_f)(1 + \lambda)$  and  $\gamma =$  $\frac{2}{3}\pi^2 k_{\rm B}^2 N(E_{\rm f}) (1+\lambda)$ , it is expected that  $T_c$  is closely related to  $\gamma$  and  $N^*(E_f)$ . Here  $k_B$  is Boltzmann's constant. Fig. 11 shows the relation between  $T_{c}$  and  $\gamma$  for the  $Zr_{85}Si_{15-x}M_{x}$  (M = B, Al ,C, Ge or Sn) alloys. Although a completely linear relation is not well satisfied in both the parameters, it can be seen that the values of  $\gamma$  reflect on  $T_c$ : that is, the larger the values of  $\gamma$  and/or  $N^*(E_f)$ , the higher is  $T_{\rm c}$ . It is therefore concluded that the rise of  $T_{\rm c}$ with the substitution of B, Al, C or Sn for Si is due to the increase in  $\gamma$  and/or  $N^*(E_f)$ . On the other hand, the lowest  $T_c$  value of the  $Zr_{85}Ge_{15}$  alloy is attributed to the low values of  $\gamma$  and  $N^*(E_f)$ . Although the reason for the increase in  $\gamma$  and  $N^*(E_f)$  with the substitution of B, Al, C or Sn for Si is not clear at present, it may be due to the result that the interaction between metal and metalloid atoms is weaker for Zr-(B, Al, C or Sn)than for Zr-(Si or Ge) evidence for which is obtained from the facts that an amorphous phase is obtained only in Zr-Si [14] and Zr-Ge [15] alloys and the value of  $(T_p - T_e)/X_e$  corresponding to the slope of the liquidus line is larger for the latter alloys [21]. Here  $T_{\rm p}$  is the melting point of

$i_{1,5}$ and $Zr_{85}Si_{1,5}xM_x$ (M = B, C, Al, Ge or Sn) amorphous alloys	$ \begin{array}{ccccc} (\mathrm{d} H_{c_2}/\mathrm{d} T) T_{c} & \gamma & N^{*}(E_{\mathbf{f}}) & \kappa & \xi_{\mathbf{GL}}(0) & \lambda_{0} & D \\ \mathrm{A}  \mathrm{m}^{-1}  \mathrm{K}^{-1}) & (\mathrm{J}  \mathrm{m}^{-3}  \mathrm{K}^{-2}) & \times 10^{47} & (\mathrm{nm}) & (\mathrm{nm}) & (\mathrm{nm}) & (\mathrm{nm})^{2}  \mathrm{sec}^{-1}) \\ & & (\mathrm{states}  \mathrm{m}^{-3}  \mathrm{J}^{-1}  \mathrm{spin}^{-1}) \end{array} $	$30 \times 10^6$ 239 1.91 100 7.6 1050 38.0	$.04 \times 10^6$ 272 2.17 $82$ 7.3 $834$ 42.9	.19×10 <sup>6</sup> 267 2.13 89 7.6 950 39.9	.11 × 10 <sup>6</sup> 282 2.25 84 7.3 857 41.5	$.97 \times 10^6$ 276 2.20 78 7.7 850 44.4	$.29 \times 10^{6}$ 229 $1.82$ $1.82$ $101$ $7.8$ $1090$ $38.2$	$97 \times 10^6$ 271 2.16 80 7.1 793 44.2
erconducting and the related properties of $Zr_{85}Si_{15}$ and $Zr_{85}Si_{15-x}M_x$ (M = B, C, Al, Ge or Sn) amorphous allo	$N^*(E_f)$ × 10 <sup>47</sup> (states m <sup>-3</sup> J <sup>-1</sup> spin <sup>-1</sup> )	1.91	2.17	2.13	2.25	2.20	1.82	2.16
	γ (J m <sup>-3</sup> K <sup>-2</sup> )	239	272	267	282	276	229	271
	$\frac{-(\mathrm{d}H_{\mathrm{c}2}/\mathrm{d}T)}{(\mathrm{A}\mathrm{m}^{-1}\mathrm{K}^{-1})}$	2.30 × 10 <sup>6</sup>	$2.04 \times 10^{6}$	$2.19 \times 10^{6}$	$2.11 \times 10^{6}$	$1.97 \times 10^{6}$	$2.29 \times 10^{6}$	$1.97 \times 10^{6}$
	ρ <mark>n</mark> , 4.2 K (μΩm)	2.70	2.10	2.30	2.10	2.00	2.80	2.05
	$\Delta T_{c}(\mathbf{K})$	0.05	0.07	0.10	0.08	0.10	0.05	0.08
	<i>T</i> <sub>c</sub> (K)	2.71	3.33	2.81	3.16	3.06	2.59	3 59
TABLE I Sup	Alloy (at %)	Zr Si		Zr Si Al	ZrSiAl.	Zr_Si_C	ZrGe.	Zr. Si Sn.

 $M_{r}$  (M = B, C, Al, Ge or Sn) amorphous alloys and Zr .- Si. and the related properties of Zr.-Si-. - +i-- -....

Zr,  $T_e$  is the eutectic temperature and  $X_e$  is the eutectic composition represented in at%. The weak interaction is considered to result in an increase in the number of atoms contributing to the superconductivity through the decrease in the number of atoms which contribute to the covalent-like bonding between metal and metalloid atoms. It is well known that the larger the interaction among the constituent elements in alloys and the steeper the slope of the liquidus line the easier is the amorphous-phase formation of the alloys.

Furthermore, one can notice the tendency that  $T_c$  rises with decreasing residual electrical resistivity. Such a relationship between  $T_c$  and  $\rho_n$  has also been recognized in the amorphous alloys of Zr-Si [14], Zr-Ge [15] and Zr-Nb-Si [19], etc. These results indicate that as the degree of disorder in atomic configuration increases,  $T_c$  is decreased. Therefore, it is considered that the substitution of B, Al, C or Sn for Si causes a decrease in the degree of disorder of the amorphous structure, and hence results in a rise of  $T_c$ .

As shown in Table I, by the substitution of B, Al, C or Sn for Si, the  $\kappa$  and  $\lambda_0$  decrease from 100 to 78 and 1050 to 735 nm, respectively, and D increases from 38.0 to  $44.4 \text{ m}^2 \text{ sec}^{-1}$ . No systematic change of the  $\xi_{GL}(0)$  by changing the compositions is seen and the value is about 7.4 nm. The decreases in  $\kappa$  and  $\lambda_0$  and the increase in D appear to originate from the increase of the electron mean-free path, l, due to the decrease in the degree of disordered state near atomic scale, evidence for which is given by the significant decrease in the electrical resistivity from 2.70 to 2.00  $\mu\Omega m$ . The reason for the decrease in electrical resistivity with increasing Al or Sn content for  $Zr_{85}Si_{15-x}Al_x$  and  $Zr_{85}Si_{15-x}Sn_x$  alloys appears to be caused by the decrease of the metalloid (Si) content because Al and Sn belong to metal elements. It has been demonstrated for Zr-Si [14] and Zr-Ge [15] amorphous alloys that the decrease in Si or Ge content results in a significant decrease in electrical resistivity. However, the reason for the decrease in  $\rho_n$  with the substitution of B or C for Si is considered to be different from that in the case of the substitution of Al or Sn for Si. The dissolution of B or C appears to result in a lowering of the degree of disorder by occupying the holes in the amorphous polyhedron which was constructed with Zr and Si

having atomic sizes much larger than B or C. A more detailed investigation of the structure of  $Zr_{85}Si_{15-x}M_x$  amorphous alloys will shed some light upon such a compositional dependence of  $T_c$ .

Although the values of  $\kappa$ ,  $\xi_{GL}(0)$  and  $\lambda_0$  decrease and D increases with the substitution of B, Al, C or Sn for Si, the absolute values of  $\kappa$ ,  $\xi_{GL}(0)$  and  $\lambda_0$  are extremely large and D is extremely small. These results indicate that the present  $Zr_{85}Si_{15-x}M_x$  amorphous superconductors are typical type-II materials characterized as extremely high degree of dirtiness. As described above, the decrease in the degree of dirtiness is probably because atomic configurations become less random on the scale much smaller than  $\xi_{GL}(0)$  by the substitution of B, C, Al or Sn for Si.

## 5. Conclusions

The compositional dependences of the formation range,  $H_v$ ,  $T_x$  and superconducting properties of  $Zr_{85}Si_{15-x}M_x$  and  $Zr_{85}Ge_{15-x}M_x$  (M = B, Al, C, Si, Ge or Sn) amorphous alloys prepared by the meltquenching technique were examined as a function of M content. The results obtained are summarized below.

(1) The effect of elements M on the formation tendency of the amorphous phase is very similar between  $Zr_{85}Si_{15-x}M_x$  and  $Zr_{85}Ge_{15-x}M_x$  alloys and becomes smaller in the order  $Si \simeq Ge > B \simeq Al \simeq Sn > C$ .

(2) The substitution of B, C or Al for Si or Ge results in significant increases in  $H_v$  and  $T_x$ , whereas the effect of the other elements on the increases in  $H_v$  and  $T_x$  is less significant.

(3)  $T_c$  rises with the substitution of B, Al, C or Sn for Si, whereas the substitution of Ge causes a slight lowering of  $T_c$ . Thus, the effectiveness of elements M on the rise of  $T_c$  decreases in the order of C > Al > Sn > B > Si > Ge.

(4) The  $dH_{c2}/dT$  at  $T_c$  and  $\rho_n$  decrease from  $2.30 \times 10^6$  to  $1.97 \times 10^6$  A m<sup>-1</sup> K<sup>-1</sup> and 2.70 to  $2.00 \,\mu\Omega$ m, respectively, with the substitution of B, Al, C or Sn for Si. The values of  $\gamma$ ,  $N^*(E_f)$ ,  $\kappa$ ,  $\xi_{GL}(0)$  and  $\lambda_0$  were estimated from the data of  $(dH_{c2}/dT)_{T_c}$  and  $\rho_n$  by using the extend GLAG theory, and it is concluded that the rise of  $T_c$  with the substitution of B, C, Al or Sn is attributable to the increases in  $\gamma$  and  $N^*(E_f)$  and is also clearly related to the decrease in the degree of dirtiness caused by the decrease in electrical resistivity.

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